

ABSTRACT OF THE DISCLOSURE

POLISHING HEAD AND POLISHING APPARATUS

5 A polishing head capable of preventing contact between both side walls of
an elastic membrane when a negative pressure is formed in a pressure chamber
formed by the elastic membrane. The polishing head includes: a first elastic
membrane configured to press the workpiece against the polishing pad; a retainer
ring surrounding the first elastic membrane; a second elastic membrane configured
10 to press the retainer ring against the polishing pad; a carrier to which the first elastic
membrane is secured; and an attachment member arranged in a pressure chamber
formed by the second elastic membrane and fixing the second elastic membrane to
the carrier. The attachment member has a support portion extending toward the
retainer ring along a side wall of the second elastic membrane.

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FIG. 3